

Title (en)

Process for selective deposition of a metal layer

Title (de)

Verfahren zur selektiven Abscheidung einer Metallschicht

Title (fr)

Procédé de dépôt sélectif d'une couche métallique

Publication

EP 0926262 B1 20030326 (DE)

Application

EP 98121020 A 19981105

Priority

DE 19748888 A 19971105

Abstract (en)

[origin: DE19851101A1] Site selective coupling of multi-atom polar compound (I) to surface of a polymer substrate where regions of the surface are treated with electromagnetic radiation. Components in the base material of the polymer are converted to reactive centers and brought into contact with a liquid solution of the polar compound (I) to couple (I) to the reactive centers. An Independent claim is included for a process for the selective deposition of a metal layer onto the surface of a polymer substrate comprising: (A) irradiating the areas of the surface to be coated with electromagnetic radiation to produce reactive centers; (B) fixing the reactive functional groups on the surface with a noble metal compound by contact with a solution of one or more noble metal compounds (II); (C) depositing the metal layer in an electroless plating bath.

IPC 1-7

C23C 18/16

IPC 8 full level

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CPC (source: EP)

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Cited by

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